

jc879 u.s. x10  
9/945116  
01/26/01

430	30
	Subclass
	Class

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**PATENT NUMBER**

**U.S. UTILITY Patent Application**

**O.I.P.E.**

**PATENT DATE**

SCANNED

Q.A.

APPLICATION NO. 09/945316	CONT/PRIOR	CLASS 430	SUBCLASS 30	ART UNIT 1756	EXAMINER Young
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## APPLICANTS

Ulrich Boettiger  
Scott Light

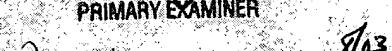
TITLE

Method and apparatus for controlling radiation beam intensity directed to microlithographic substrates

(as amended by C.R. 2080)

## **ISSUING CLASSIFICATION**

Continued on Issue Slip Inside File Jacket

TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	6	8	None	39	1
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____				NOTICE OF ALLOWANCE MAILED	
	(Assistant Examiner)		(Date)	6/13/03	
				ISSUE FEE	
	CHRISTOPHER G. YOUNG PRIMARY EXAMINER		(Primary Examiner)	Amount Due	Date Paid
			8103	1600.00	
<input type="checkbox"/> The terminal _____ months of				ISSUE BATCH NUMBER	
				8230	

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